

Korejský úřad duševního vlastnictví

Patentová databáze



Jarmila Avratová, ÚPV

http://www.kipo.go.kr

**KIPO**
KOREAN INTELLECTUAL PROPERTY OFFICE

twitterHOME SITE MAP CONTACT US KOREAN RELATED SITES

Search

About KIPO **KIPO's Activities** Patents & Utility Models Trademarks & Designs PCT Service Public Relations Resources

IP Examination | International Affairs | IP Training & Education | IP & Development | IP Office Automation | IP Protection



Signing Ceremony For MOU between UAE and KIPO

MOU between UAE and KIPO Consortium
Feb. 23, 2016 Seoul, Korea

KIPO NEWS + more [Subscribe](#)

[Applications are being accepted for entry int...](#)
KIPO and the Korea Women Inventors Association (KW...
March 23, 2017

[The Republic of Korea strengthens its cordial...](#)
- KIPO opened the Ylang Ylang Herb Oil Center in t...
March 14, 2017

[KIPO Issues IP Policies to APEC](#)
- KIPO developed the "Guidebook for SMEs' IP-Busin...
February 24, 2017

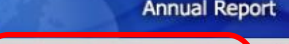
[KIPO opened the Yla...](#)
KIPO opened the Ylang Ylang He



Commissioner's Message



Introduction to KIPO



Annual Report

Intellectual Property Information Search

Korean Patent Abstracts

1020050012345, phone

Search

For detailed searches, please visit KIPRIS Web site

KIPO's Activities

IP Examination

International Affairs

· Bilateral & Multilateral Cooperations

· Patent Prosecution Highway

IP Training & Education

· International IP Courses

· IP e-Learning

IP & Development

· WIPO Korea Funds-in-Trust

· Appropriate Technology / AT Competition

· One Village One Brand

IP Office Automation

Patents & Utility Models

Korean Patent System

Korean Utility Model System

Application Procedure for Patents and Utility Models

Application Procedure for Layout Designs

Appeals & Trials

Fees and Payments

Trademarks & Designs

Korean Trademark System

Korean Design System

Application Procedure for Trademarks

Application Procedure for Designs

Fees and Payments

Resources

Industrial Property

Statistical Information

Publications

Forms

Intellectual Property Information Search

Korean Patent Abstracts

1020050012345, phone

Search

For detailed searches, please visit KIPRIS Web site



Why Korea needs to host a WIPO External Office

WIPO Korea Funds-in-Trust

 IP e-learning portal

**IIPTI**
International Intellectual Property Training Institute

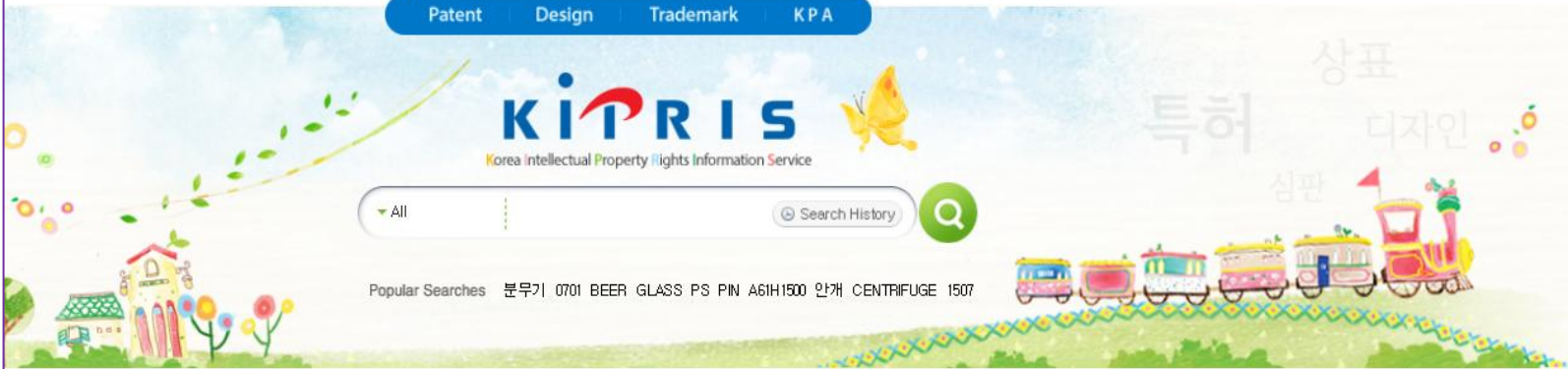
 **PATENT COURT OF KOREA**

<http://eng.kipris.or.kr/enghome/main.jsp>



[SEARCH](#)
[TODAY KIPRIS](#)
[PR](#)
[GUIDE](#)
[KIPRIS](#)

[Patent](#)
[Design](#)
[Trademark](#)
[KPA](#)



Popular Searches: 분무기 0701 BEER GLASS PS PIN A6IH1500 안개 CENTRIFUGE 1507



TUTORIAL



Brochure



Manual



Beginner's Program
Guided Search for Beginners



KIPRIS
Introduction to KIPRIS



Translation Companies
Patent translation companies in Korea

NOTICE , more

KPA Bibliography is now available(Pat...	2017-02-22
KPA Bibliography is now available(Pat...	2017-01-20
KPA Bibliography is now available(Pat...	2016-12-22
KPA Bibliography is now available(Pat...	2016-11-21

Other Service

- KPA Publication
- Electronic Data Bank
- Korean IP Translation companies

Search Guide

- Data coverage
- Viewer Downloads & Installations
- Q&A

Reference

- KIPO Publications
- Statistics
- Korean IP System(Link to KIPO)
- Others

KIPRIS

- About KIPRIS
- NEWS
- Location & Map

RELATED SITES

- Patent Search Websites
- IP Related Organizations in Korea
- Other IPOs




Government Complex-Daejeon Building 4,
189 Cheongsu-ro, Seo-gu, Daejeon, Korea (35208)
Copyright (C) 1996-2009 Korean Intellectual Property Office. All Rights Reserved.



Rychlé vyhledávání

The screenshot shows the KIPRIS patent search interface. Red circles and rectangles highlight several key features:

- Search Bar:** The search term "aerogel+rice" is entered in the search bar.
- Search History:** The "Search History" link is highlighted in the top navigation bar.
- Advanced Search:** The "Click here! for advanced search" link is highlighted in the top navigation bar.
- Category:** The "Category" section on the left sidebar is highlighted, showing filters for Patent, Utility model, Registered, Unexamined, etc.
- Help:** The "Help" link in the right sidebar is highlighted.

The main search results display the following information:

- Total 5 Articles (1 / 1 Pages)**
- [1] LOW COST ROUTES TO HIGH PURITY SILICON AND DERIVATIVES THEREOF** (고순도 실리콘을 생산하기 위한 저비용 제조방법 및 이의 유도제)
 - IPC: C01B 33/037 C01B 33/023
 - Applicant: MAYATERIALS, INC.
 - Application No.: 1020117005049
 - Application Date: 2011.03.03
 - Registration No.: 1013881460000
 - Registration Date: 2014.04.16
 - Unex. Pub. No.: 1020110049852
 - Unex. Pub. Date: 2011.05.12
 - Agent: PHIL & ONZI INT'L PATENT & LA...
 - Inventor: LAINE, Richard, M. | KRUG, David, James | MARCHAL,...
- [2] THREE-DIMENSIONAL, PREVASCULARIZED, ENGINEERED TISSUE CONSTRUCTS, METHODS OF MAKING AND METHODS OF USING THE TISSUE CONSTRUCTS** (삼차원, 예비맥관화, 조직 조직 구조체, 조직 구조체의 제조 방법 및 사용 방법)
 - IPC: C12M 3/00 B81B 1/00
 - Applicant: The UAB Research Foundation
 - Application No.: 1020147027940
 - Application Date: 2014.10.02
 - Registration No.:
 - Registration Date:
 - Unex. Pub. No.: 1020140142278
 - Unex. Pub. Date: 2014.12.11
 - Agent: Kim Jin Hoe
 - Inventor: BERRY, Joel, L. | WICK, Timothy, M. | MURPHY-ULLRI...
- [3] RADIANT HEATER IN PARTICULAR FOR HEATING A GLASS CERAMIC HOT PLAT** (글라스-세라믹제 가열판을 가열하는 방열기)
 - IPC: H05B 3/74
 - Applicant: WACKER CHEMIE AG
 - Application No.: 1019940022651
 - Application Date: 1994.09.08
 - Registration No.: 1001598020000
 - Registration Date: 1998.08.13
 - Unex. Pub. No.: 1019950010690
 - Unex. Pub. Date: 1995.04.28
 - Agent: YOU ME PATENT & LAW FIRM
 - Inventor: Q | EYHORN, THOMAS | Q | Q-
- [4] METHOD AND SYSTEM FOR INERTING A WALL OF A LIQUEFIED FUEL GAS-STORAGE TANK** (액화 연료 가스 저장 탱크 벽체의 불활성화 방법 및 시스템)
 - IPC: F17C 3/10 F17C 13/02
 - Applicant: GAZTRANSPORT ET TECHNIQ A7

The right sidebar contains the following sections:

- Help:** Q&A, Data Coverage, Save Query, View My Folder, Save My Folder, Save All My Folder, Online Download.
- Real-time popular keyword:** Today KIPRIS +
 - 1 PS
 - 2 A61H1500
 - 3 CENTRIFUGE
 - 4 A21D
 - 5 CELL
 - 6 A21D13
 - 7 COLLECTION
 - 8 JP
 - 9 A21D10
 - 10 FAT
- Recently viewed patent:**
 - [THREE-DIMENSIONAL](#)
Appl. No.: 1020147027940
 - [LOW COST ROUTES TO](#)
Appl. No.: 1020117005049

LOW COST ROUTES TO HIGH PURITY SILICON AND DERIVATIVES THEREOF

고순도 실리콘을 생산하기 위한 저비용 제조방법 및 이의 유도체

Details Unexam. Full Text Publ. Full Text Registr. Details Administrative

Details Biographical Information Legal Status Claim Designated States Prior Art Document(s) Family Patent

(51) Int. CL C01B 33/037(2011.05.09) C01B 33/023
(2014.02.18) B09B 3/00(2014.02.18) C22B 7/00
(2014.02.18)

(52) CPC

(21) Application No.(Date) 1020117005049 (2011.03.03)

(71) Applicant MAYATERIALS, INC.

Translation submission Date (2011.03.03)

(11) Registration No.(Date) 1013881460000 (2014.04.16)

(65) Unex. Pub. No.(Date) 1020110049852 (2011.05.12) Full-doc Down

(11) Publication No.(Date) (2014.04.29) Full-doc Down

(86) Int'l Application No.(Date) PCT/US2009/052965(2009.08.06)

(87) Int'l Unex. Pub. No.(Date) WO2010017364(2010.02.11)

(30) Priority info. 미국(US) | 61/086,546 | 2008.08.06
(Country / No. / Date)

Legal Status Registered

Examination Status Decision to grant (General)

Trial Info

Kind/Right of Org. Application International Application /

Right of Org. Application No.
(Date)

Related Application No.

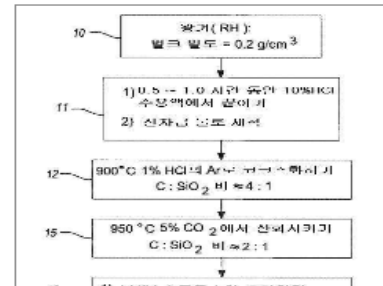
Request for an examination Y(2011.03.03)
(Date)

Number of examination claims 25

Abstract (Machine Translation)

The invention relates to the amorphous silica, and carbon and containing impurities, the step of extracting the impurities of the waste, the step of diversifying the ratio of the carbon large silica, and the step of returning cell silicone) for silica.

Bibliografie



LOW COST ROUTES TO HIGH PURITY SILICON AND DERIVATIVES THEREOF

고순도 실리콘을 생산하기 위한 저비용 제조방법 및 이의 유도체

Details Unexam. Full Text Publ. Full Text Registr. Details Administrative

Machine Translation

1 / 27 61.4%

Nástroje Vyplnit a podepsat Rozměr

Záložky

- 문서
 - 서지사항
 - 요약
 - 대표도
 - 특허청구의 범위
 - 명세서
 - 기술 분야
 - 배경 기술
 - 발명의 내용
 - 해결하려는 과제
 - 과제의 해결 수단
 - 발명의 효과
 - 도면의 간단한 설명
 - 발명을 실시하기 위한 구체적인 내용
 - 도면
 - 도면1
 - 도면2
 - 도면3

등록번호 10-1388146

(19) 대한민국특허청(KR)
(12) 등록특허공보(B1)

(61) 국제특허문헌(Int. Cl.) C01B 33/037(2011.05.09) C01B 33/023(2011.05.09)
(21) 출원번호 10-2011-0049852
(22) 출원일자(국제) 2011년03월03일
(86) 국제출원번호 PCT/US2009/052965
(87) 국제출원번호 WO 2010/017364
(88) 국제출원번호 PCT/US2009/052965
(89) 국제출원번호 PCT/US2009/052965
(90) 우선권주장 61/086,546 2008년08월06일 미국(US)
(66) 선행기술문헌
US20070217988 A1
US4440558 A
US6414920 A
US20060009258 A1
*는 심사관에 의해 인용된 문헌

본 발명은, 무정형 실리콘, 탄소 및 불순물들을 함유하는 농업 폐기물을 분리하는 단계; 상기 농업 폐기물로부터 상당량의 불순물들을 추출하는 단계; 탄소 대 실리콘의 비율 변화시키는 단계; 및 상기 실리콘을 고순도 실리콘(예를 들어, 태양전지 실리콘)으로 변환하는 단계를 포함하는 방법에 대한 것이다.

요약

본 발명은, 무정형 실리콘, 탄소 및 불순물들을 함유하는 농업 폐기물을 분리하는 단계; 상기 농업 폐기물로부터 상당량의 불순물들을 추출하는 단계; 탄소 대 실리콘의 비율 변화시키는 단계; 및 상기 실리콘을 고순도 실리콘(예를 들어, 태양전지 실리콘)으로 변환하는 단계를 포함하는 방법에 대한 것이다.

대표도 - 51

```

graph TD
    A["10: 불활성(RH)  
밀도 = 0.2 g/cm³"] --> B["11: 1) 0.5 ~ 1.0 중량 퍼센트 10% HCl  
수용액에서 침출하기  
2) 산화물 침출 제거"]
    B --> C["12: 900°C 1% HCl에서 처리하기  
C:SiO₂ 비 ≈ 4:1"]
    C --> D["15: 950°C 5% CO₂에서 산화시키기  
C:SiO₂ 비 ≈ 2:1"]
    
```


Claim 3:

Bibliografie

Bibliographic Data

Int.Cl.	C01B 33/037 C01B 33/023 B09B 3/00 C22B 7/00
Published Date	20140429
Registration No.	1013881460000
Registration Date	20140416
Application No.	1020117005049
Application Date	20110303
Unexamined Publication No.	1020110049852
Unexamined Publication Date	20110512
Priority Claims	61/086,546 20080806 US
Requested Date of Examination	20110303
Agent.	PHIL & ONZI INT'L PATENT & LAW FIRM
Inventor	LAINE, Richard, M. KRUG, David, James MARCHAL, Julien, Claudius MCCOLM, Andrew, Stewart
Applicant	MAYATERIALS, INC.
Rightholder	MAYATERIALS, INC.

발명의 명칭

고순도 실리콘을 생산하기 위한 저비용 제조방법 및 이의 유도체

Title of Invention

The low-cost production method and its derivative for producing the high purity silicon.

요약

Abstract

LOW COST ROUTES TO HIGH PURITY SILICON AND DERIVATIVES THEREOF

고순도 실리콘을 생산하기 위한 저비용 제조방법 및 이의 유도체

Details	Unexam. Full Text	Publ. Full Text	Registr. Details	Administrative
---------	-------------------	-----------------	-------------------------	----------------

Right Information		
Indication Number	Details	
No.1	Application Date : 2011. 03. 03 Date of Priority Claim : 2008. 08. 06 Country of Priority Claim : United States of America Issue Date : 2014. 04. 29 Date of Decision to Grant Registration (Trial Decision) : 2014. 02. 19 Classification : C01B 33/037 Title of Invention : LOW COST ROUTES TO HIGH PURITY SILICON (Expected)Date of Expiration : 2029. 08. 06	Application Number : 10-2011-7005049 Number of Priority Claims : 1 Publication Number : Number of Claims :

Položky řízení

Patentee Information	
Priority Number	Details
No.1	(Right Holder) 마테리얼스, 아이엔씨. 미국, 미시건 ***** , 앤 알보, **** 포크스톤 코트

※ We provide limited information for protection of personal information.
 ※ We ask you to check the corresponding information by getting a copy of the original register or provide all information (e.g. exclusive licensee, non-exclusive licensee, etc.)

Registraion Fee Information	
-----------------------------	--

LOW COST ROUTES TO HIGH PURITY SILICON AND DERIVATIVES THEREOF

고순도 실리콘을 생산하기 위한 저비용 제조방법 및 이의 유도체

Details	Unexam. Full Text	Publ. Full Text	Registr. Details	Administrative
---------	-------------------	-----------------	------------------	-----------------------

▶ Administrative Actions

No.	Document Title	Receipt/Delivery Date	Status	Receipt/Delivery No.
1	[Patent Application] Document according to the Article 203 of Patent Act ([특허출원]특허법 제203조에 따른 서면)	2011.03.03	Accepted (수리)	112011015304751
2	Notice of Acceptance (수리안내서)	2011.03.09	Completion of Transmission (발송처리완료)	152011002040657
3	Notification of reason for refusal (의견제출통지서)	2013.02.26	Completion of Transmission (발송처리완료)	952013013187213
4	[Amendment to Description, etc.] Amendment ([명세서등 보정]보정서)	2013.04.26	Regarded as an acceptance of amendment (보정승인간주)	112013037104306
5	[Opinion according to the Notification of Reasons for Refusal] Written Opinion (Written Reply, Written Substantiation) ([거절이유 등 통지에 따른 의견]의견(답변, 소명)서)	2013.04.26	Accepted (수리)	112013037104115
6	Notification of reason for refusal (의견제출통지서)	2013.08.28	Completion of Transmission (발송처리완료)	952013059639417
7	[Amendment to Description, etc.] Amendment ([명세서등 보정]보정서)	2013.10.24	Regarded as an acceptance of amendment (보정승인간주)	112013096375413

Bibliographic Abstract Drawing Claims Description

A A A

Příčemž nabitý 1:

Příprava amorfní oxid křemičitý, zemědělský odpad, který obsahuje uhlík a nečistoty, a v tomto okamžiku, zemědělské odpady je spalovat kroky odpadního materiálu výrobku v zemědělství;

Krok extrakce významná množství nečistot kyselého vodného roztoku ze zemědělského odpadu, tvořící extrakci zemědělského odpadu;

Změnou molární poměr uhlíku na oxid křemičitý čisté zemědělské odpady: (čistý odpadní produkt zemědělský VHP d) připravit a); A

způsob výroby vysoce čistého křemíku, který zahrnuje krok snížení oxidu křemičitého na křemíkových solárních platby buněk.

Ve kterém nabitý 2:

Způsob podle nároku 1, kde

v kroku přípravy zemědělského odpadu, nebo mletí za účelem zvýšení expozice pórů zemědělských odpadů, způsob výroby vysoce čistého křemíku, vyznačující se tím, že síťové hodnot nebo usazovací nebo prochází jako u kombinované léčby,

Billing 3:

Způsob podle nároku 1, kde

v kroku přípravy zemědělského odpadu, zemědělský odpad, je 95 až způsob výroby vysoce čistého molární poměr v rozmezí od 60: 40.

Nabitá 4:

Způsob podle nároku 1, vyznačující se tím,

v kroku přípravy zemědělského odpadu, způsob zemědělský odpad z výroby vysoce čistý křemík, vyznačující se tím, že obsahuje oxid křemičitý alespoň 40% hmotnostních.

Nabitá 5:

vymazání

Nabitá 5:

vymazání

**Původní text**

제1항에 있어서, 농업 폐기물을 준비하는 단계에서, 농업 폐기물의 공의 노출을 증가시키기 위하여 분쇄되거나, 체로 치거나, 침전되거나, 또는 이들의 조합된 처리를 거치는 것을 특징으로 하는 고순도 실리콘의 제조방법.

[Navrhnout lepší překlad](#)

Pokročilé vyhledávání

View Save Query  Eng-Kor		Patent aerogel 		 Search within search results ☐																																								
Search History aerogel hyaluron+acid		< >																																										
Click help or guide for more information																																												
Right	☒ Patent ☒ Utility model																																											
Status	☒ Entire ☒ Rejected ☒ Registered ☒ Ended ☒ Invalidated ☒ Withdrawn ☒ Abandoned ☒ Unexamined																																											
Free Search (Full Text) help	aerogel		and ▼																																									
IPC guide	C01B33		x and ▼																																									
CPC guide	ex)G06Q		and ▼																																									
Number guide	<table border="0"> <tr> <td>Application No.(AN)</td> <td> ex) 1020020012345 </td> <td>and ▼</td> <td>Registration No.(GN)</td> <td> ex) 100012345 </td> <td>and ▼</td> <td rowspan="4"></td> </tr> <tr> <td>Unex. Pub. No.(OPN)</td> <td> ex) 1020020012345 </td> <td>and ▼</td> <td>Publication No.(PN)</td> <td> ex) 1019800001264 </td> <td>and ▼</td> </tr> <tr> <td>Int'l Application No.(FN)</td> <td> ex) PCT/US2002/019728 </td> <td>and ▼</td> <td>Int'l Unex. Pub. No.(FON)</td> <td> ex) WO2003008308 </td> <td>and ▼</td> </tr> <tr> <td>Priority No.(RN)</td> <td> ex) KR2020030030648 </td> <td>and ▼ </td> <td></td> <td></td> <td></td> </tr> </table>				Application No.(AN)	ex) 1020020012345	and ▼	Registration No.(GN)	ex) 100012345	and ▼		Unex. Pub. No.(OPN)	ex) 1020020012345	and ▼	Publication No.(PN)	ex) 1019800001264	and ▼	Int'l Application No.(FN)	ex) PCT/US2002/019728	and ▼	Int'l Unex. Pub. No.(FON)	ex) WO2003008308	and ▼	Priority No.(RN)	ex) KR2020030030648	and ▼ 																		
Application No.(AN)	ex) 1020020012345	and ▼	Registration No.(GN)	ex) 100012345	and ▼																																							
Unex. Pub. No.(OPN)	ex) 1020020012345	and ▼	Publication No.(PN)	ex) 1019800001264	and ▼																																							
Int'l Application No.(FN)	ex) PCT/US2002/019728	and ▼	Int'l Unex. Pub. No.(FON)	ex) WO2003008308	and ▼																																							
Priority No.(RN)	ex) KR2020030030648	and ▼ 																																										
Date guide	<table border="0"> <tr> <td>Publication Date(PD)</td> <td> ex) 20101130 </td> <td>~</td> <td> ex) 20101130 </td> <td>and ▼</td> <td>Application Date(AD)</td> <td> </td> <td>~</td> <td> </td> <td>and ▼</td> </tr> <tr> <td>Registration Date(GD)</td> <td> </td> <td>~</td> <td> </td> <td>and ▼</td> <td>Unex. Pub. Date(OPD)</td> <td> </td> <td>~</td> <td> </td> <td>and ▼</td> </tr> <tr> <td>Int'l Application Date(FD)</td> <td> </td> <td>~</td> <td> </td> <td>and ▼</td> <td>Int'l Unex. Pub. Date(FOD)</td> <td> </td> <td>~</td> <td> </td> <td>and ▼</td> </tr> <tr> <td>Priority Date(RD)</td> <td> </td> <td>~</td> <td> </td> <td>and ▼</td> <td></td> <td></td> <td></td> <td></td> <td></td> </tr> </table>				Publication Date(PD)	ex) 20101130	~	ex) 20101130	and ▼	Application Date(AD)		~		and ▼	Registration Date(GD)		~		and ▼	Unex. Pub. Date(OPD)		~		and ▼	Int'l Application Date(FD)		~		and ▼	Int'l Unex. Pub. Date(FOD)		~		and ▼	Priority Date(RD)		~		and ▼					
Publication Date(PD)	ex) 20101130	~	ex) 20101130	and ▼	Application Date(AD)		~		and ▼																																			
Registration Date(GD)		~		and ▼	Unex. Pub. Date(OPD)		~		and ▼																																			
Int'l Application Date(FD)		~		and ▼	Int'l Unex. Pub. Date(FOD)		~		and ▼																																			
Priority Date(RD)		~		and ▼																																								
Text	<table border="0"> <tr> <td>Title of Invention(TL)</td> <td><input cellularphone"="" type="text" value="ex) phone touch screen, electronic*cash, "/></td> <td>and ▼</td> <td rowspan="3"></td> </tr> <tr> <td>Abstract(AB)</td> <td><input datasignal"="" type="text" value="ex) car + clutch, "/></td> <td>and ▼</td> </tr> <tr> <td>Claims(CL)</td> <td><input datasignal"="" type="text" value="ex) car + clutch, "/></td> <td>and ▼</td> </tr> </table>				Title of Invention(TL)	<input cellularphone"="" type="text" value="ex) phone touch screen, electronic*cash, "/>	and ▼		Abstract(AB)	<input datasignal"="" type="text" value="ex) car + clutch, "/>	and ▼	Claims(CL)	<input datasignal"="" type="text" value="ex) car + clutch, "/>	and ▼																														
Title of Invention(TL)	<input cellularphone"="" type="text" value="ex) phone touch screen, electronic*cash, "/>	and ▼																																										
Abstract(AB)	<input datasignal"="" type="text" value="ex) car + clutch, "/>	and ▼																																										
Claims(CL)	<input datasignal"="" type="text" value="ex) car + clutch, "/>	and ▼																																										

Nápověda

Classification		Description	example
Word search		Find results that include one or more instances of a word you specify	disc
Phrase search("")		Find results that include a phrase you specify	"data signal"
Logical operator	AND(+)	Find results with all the search elements you specify	Cellular phone+case
	OR(+)	Find results with at least one of search elements you specify	Cellular phone+ mobile phone
	NOT(!)	Find results without the elements you specify	Car*!clutch
	NEAR(^)	Find results in which two or more search terms have to appear within a specified number of words of each other	Car^2angle (within 2 words form car; n is from 1 to 3)
	Truncation (?)	Patent/Utility Model search with partial number information (This can be used for number searches only. For help, please refer to 'Patnet help -> Smart Search -> Search by Number'.)	?-2012-0001234



Search within
Search Results

'Search within Search Results' can be found at the top of the screen by the search box. It is useful when you want to narrow down the results within the preliminary results.

Data Coverage View

Database Contents

Application Date

Unex. Pub. Date

Publication Date

Registration Date

IPC

Statistics

Database is updated daily but some data can be missed from the update.

Database covers the data from 1948 to today.

Types	Recode Date	Duration	Count
Pat. Unexam Pub.	Unex. Pub. Date	1983.03.25 ~ 2017.04.06	2,750,430
Pat. Pub.	Pub. Date	1948.06.20 ~ 2017.04.06	1,699,787
Util. Model Unexam. Pub.	Unex. Pub. Date	1983.03.25 ~ 2017.04.06	579,164
Util. Model Pub.	Pub. Date	1948.06.20 ~ 2017.04.06	508,246



Europäisches
Patentamt
European
Patent Office
Office européen
des brevets

Search

Website

Patents

Home

Searching for patents

Applying for a patent

Law & practice

News & issues

Learn

Home > Searching for patents > **Helpful resources**

First time here?

**Asian patent
information**

Events, training and
publications

Patent information
centres

Raw data

Information on EPO
data

Patent Translate

Can't find a product?

Fair use charter

Helpful resources

> First time here?

Find out what patent information is and how to use it.

> Events, training and publications

Learn more about our events, conference, e-learning, training, and key publications.

Asian patent information

Translation services

China (CN)

Chinese Taipei (TW)

GCC FAQ

India (IN)

Japan (JP)

Korea (KR)

FAQ

Facts and figures

Grant procedure

Numbering system

Useful terms

Searching in
databases

Saudi Arabia (SA) FAQ

Updates

Korea (KR)

In 2007, Korean patent literature became part of the PCT minimum documentation and must be included in patentability searches done for PCT applications. This area provides background information on the Korean patent system and guidance on other essentials of Korean patent documentation. See the Searching in databases section for tips on how to search sources of Korean patent information.

> FAQ

Answers to common questions about patents and patent information in Korea. If you cannot find the answer you are looking for, you can write to us using our [form](#).

> Grant procedure

A flowchart overview of the most important steps in the Korean procedures from filing an application to the grant of a patent.

> Useful terms

Some common patent terms in Korea

> Facts and figures

Developments in filing figures and application trends in Korea.

> Numbering system

An introduction to the most important document types (including kind codes) and explanations of the formats for document numbers.

> Searching in databases

Tips and tricks for using free Korean data sources without knowing the language. Simple, step-by-step search guides demonstrate how to make the

Číselný systém

Search services	
Translation services	
China (CN)	
Chinese Taipei (TW)	
India (IN)	
Japan (JP)	
Korea (KR)	
FAQ	
Facts and figures	
Grant procedure	
Numbering system	
Useful terms	
Searching in databases	
Saudi Arabia (SA) FAQ	
Patent trends	
Updates	
Useful links	

Numbering system - Korea

Document and kind codes

GONGGAE (A, U) - [enlarge](#)

공개

- unexamined patent publication (A)
- unexamined utility model publication (U)

GONGGO (B, Y) - [enlarge](#)

공고

- examined patent publication (old law) (B)
- examined utility model publication (old law) (Y)

DEUNGNOK (B, Y) - [enlarge](#)

등록

- granted patent publication (B)
- registered utility model publication (Y)

Number formats

application numbers:

yy-nnnnnn(n)

(between 1948 and 1993)

- two digits for the year (y)
- six or seven digits for the serial number (n)

yyyy-nnnnnn(n)

(between 1994 and 1997)

- four digits for the year (y)
- six or seven digits for the serial number (n)

tt-yyyy-nnnnnnn

(from 1998 onwards)

- two digits for the type of right (t)
- four digits for the year (y)
- seven digits for the serial number (n)

A-/U-publication numbers:

yy-nnnnnn(n)

(between 1983 and May 1998)

- two digits for the year (y)
- six or seven digits for the serial number (n)

yyyy-nnnnnn(n)

(between May 1998 and 2003)

- four digits for the year (y)
- six or seven digits for the serial number (n)

tt-yyyy-nnnnnnn

(from 2004 onwards)

- two digits for the type of right (t)
- four digits for the year (y)
- seven digits for the serial number (n)

Useful terms - Korea

The list below gives you the English transliteration and translation of some Korean terms typically encountered in a patent information context.

If you would like to see a bigger version of the Korean characters, please click on "enlarge".

Užitečné výrazy

Korean		Pronunciation	English
초록	enlarge	chorok	abstract
출원인	enlarge	chulwonin	applicant
출원서	enlarge	chulwonseo	application
도면의 간단한 설명	enlarge	domyeon-ui gandanhan seolmyeong	brief explanation of drawings
청구항(청구범위)	enlarge	cheongguhang (cheonggu beomwi)	claims
출원일자	enlarge	chulwon ilja	date of filing
일	enlarge	il	day
상세한 설명	enlarge	sangsehan seolmyeong	description
의장	enlarge	uijang	design
도면	enlarge	domyeon	drawings
실시	enlarge	silsi	embodiments
특허공고	enlarge	teukheo gonggo	examined patent publication
심사관	enlarge	simsagwan	examiner
권리자	enlarge	gwanllija	holder of patent right

Searching in databases - Korea

Tips & tricks for searching in databases

Easy, step-by-step instructions on how to use official Korean databases. Click on the links below to download the respective search guides.

Number search and document retrieval

- ☐ **Retrieving Korean full text data from KIPRIS** (PDF, 622 KB)
- ☐ **"Patent of my concern" - free monitoring tool for Korean publications in KIPRIS** (PDF, 723 KB)
- ☐ **Searching Korean prior art using the 'cross lingual retrieval' function in KIPRIS** (PDF, 262 KB)
- ☐ **Searching information on similar patents in KIPRIS** (PDF, 467 KB)
- NEW: ☐ **Monitoring lapsed and expired Korean patents** (PDF, 581 KB)

English machine translations

- ☐ **Retrieving free English machine translations in KIPRIS** (PDF, 650 KB)

Legal status information

- ☐ **Searching Korean file wrapper information in KIPO's OPD platform** (PDF, 865 KB)
- ☐ **Searching information on trial proceedings in KIPRIS** (PDF, 542 KB)

Děkuji Vám za pozornost



javratova@upv.cz

¹⁷
Úřad průmyslového vlastnictví
Antonína Čermáka 2a,
160 68 Praha 6-Bubeneč

